AMENDMENTS TO THE CLAIMS

This listing of claims replaces all prior versions, and listings, of claims in the application.

1. (Currently Amended) A positive-working lithographic printing plate precursor comprising (i) a grained and anodized aluminum support having a hydrophilic surface and (ii) a heat-sensitive oleophilic coating provided on the hydrophilic surface, wherein said coating comprises (a) a hydrophobic polymer which is soluble in an aqueous alkaline developer and (b) a dissolution inhibitor which is a water-repellent polymer and wherein said coating is capable of dissolving in said developer at a higher dissolution rate in areas of said coating which are exposed to heat or infrared light than in unexposed areas, wherein the hydrophilic surface has a surface roughness, measured by a mechanical profile method employing a contact stylus according to procedure defined in ISO 4288 and expressed as arithmetical mean center-line roughness Ra, which is less than 0.40 μm, wherein the hydrophilic surface comprises a salt of titanium, hafnium or zirconium, and wherein the water-repellant polymer is a block- or graft-copolymer of a poly(alkylene oxide) block and a block comprising siloxane and/or perfluoroalkyl units.

2. (Original) A plate precursor according to claim 1, wherein said salt comprises fluoride.

3 . (Previously Presented) A plate precursor according to claim 1, wherein said hydrophilic surface further comprises an orthophosphate.

4. (Previously Presented) A plate precursor according to claim 1, wherein said hydrophilic surface has a surface roughness, expressed as arithmetical mean center-line roughness Ra, which is less than 0.3 μm.

5. (Previously Presented) A plate precursor according to claim 1, wherein said aluminum support comprises more than 3.0 g/m^2 of aluminum oxide at the hydrophilic surface.

6. (Previously Presented) A plate precursor according to claim 1, wherein said aluminum support comprises more than 4.0 g/m^2 of aluminum oxide at the hydrophilic surface.

7. (Canceled).

8. (Previously Presented) A plate precursor according to claim 1, wherein said water-repellent polymer is present in a separate layer on top of said coating.

9. (Previously Presented) A plate precursor according to claim 1, wherein said coating further comprises another dissolution inhibitor which is an organic compound comprising an aromatic group and a hydrogen bonding site.

10. (Previously Presented) A plate precursor according to claim 1, wherein said coating further comprises a dissolution accelerator.

11. (Currently Amended) A method of making a positive-working lithographic printing plate precursor comprising the steps of

graining and anodizing an aluminum support,

treating said grained and anodized aluminum support with a solution comprising a salt of titanium, hafnium and zirconium, and

applying on said treated aluminum support a heat-sensitive oleophilic coating,

wherein said coating comprises (a) a hydrophobic polymer which is soluble in an aqueous alkaline developer and (b) a dissolution inhibitor which is a water-repellent polymer, wherein said coating is capable of dissolving in said developer at a higher dissolution rate in areas of said coating which are exposed to heat or infrared light than in unexposed areas, wherein the surface of said grained and anodized aluminum support is hydrophilic and has a surface roughness, measured by a mechanical profile method employing a contact stylus according to procedure defined in ISO 4288 and expressed as arithmetical mean center-line roughness Ra, which is less than 0.40 μm, and wherein the water-repellant polymer is a block- or graft-copolymer of a poly(alkylene oxide) block and a block comprising siloxane and/or perfluoroalkyl units.

12. (Previously Presented) A method of making a positive-working lithographic printing plate comprising the steps of

providing a positive-working lithographic printing plate precursor according to claim 1,

image-wise exposing said heat-sensitive coating to infrared light or heat, and

developing said image-wise exposed heat-sensitive coating with an aqueous alkaline developer, wherein the exposed areas of said coating dissolve in said alkaline developer at a higher dissolution rate than in unexposed areas of said coating.

13. (Canceled)